

Vol. 1: November 2002

| US Patent Nr. | Title | Assignee | Filed | Date of Patent |
|-------------------------|-------------------------------------------------------------------------------------------------------------------------------------------|----------|----------|----------------|
| 6429135 | Method of Reducing Stress Between a Nitride Spacer and a Substrate | UMC | 1/5/01 | 8/6/02 |
| 6429538 | Method for Making a Novel Graded Silicon Nitride / Silicon Oxide (SNO) Hard Mask for Improved Deep Submicrometer Semiconductor Processing | TSMC | 8/2/01 | 8/6/02 |
| 6433298 | Plasma Processing Apparatus | TEL | 9/19/00 | 8/13/02 |
| 6451647 | Integrated Plasma Etch of Gate and Gate Dielectric and Low Power Plasma Post Gate Etch Removal of High-k Residual | AMD | 3/18/02 | 9/17/02 |
| 6452400 | Method of measuring Negative Ion Density of Plasma and Plasma Processing Method and Apparatus for Carrying out the Same | TEL | 6/19/200 | 9/17/02 |
| 6455433 | Method for Forming Square-Shouldered Sidewall Spacers and Devices Fabricated | TSMC | 3/30/01 | 9/24/02 |
| 6463875 | Multiple Coil Antenna for Inductively-Coupled Plasma Generation Systems | LAM | 11/15/00 | 10/15/02 |